

ABSTRACT

A lamination device for performing a lamination method for a dry film resist as a transfer layer, comprising a substrate transport part (15), a substrate preheating part (8), a lamination part (9) and (10), an inter-substrate film processing part (3), a film feed part (2), a film accumulation part (4), a base film continuous peeling part (12, 13), and a cover film continuous peeling part (5), wherein a lamination is carried out by a pair of lamination rolls (9) and (10), part (15) being transport rolls, a base film is peeled off from a substrate after lamination, a guide roll (12) for peeling off the base film is located forward of the lamination rolls in the transport direction of the substrate, and the guide roll is free to move vertically or laterally, whereby an angle between a substrate surface and the base film being wound up, i.e., the peeling angle of the base film can be changed to any angle.

This Sheet Has Been Replaced